



## **Paul Scherrer Institut**

Tilman Rohe

**Sensors Review and Ordering** 



## **Experience with present sensors**

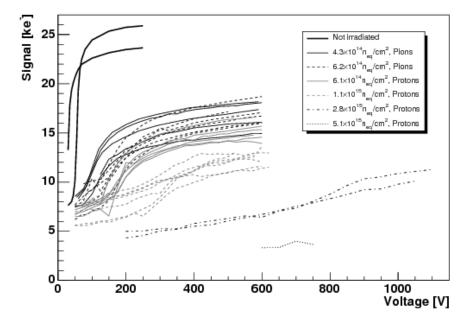
#### **CMS**

- Sensors are used for the present BPIX.
- Performance fully satisfactory
- Radiation level is still low but above the point of space charge sign ("type") inversion

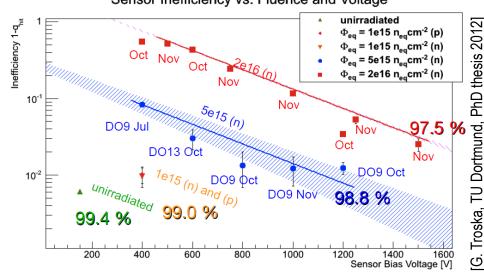
#### **Radiation hardness studies**

- Up to  $\sim 1.2 \times 10^{15} N_{eq}/cm^{-2}$ :
  - Several test beam studies in the years 2002-06
  - Including tilt angle, B-field, and threshold
  - Summarized in NIM A 583 (2008) 25-41
- Higher fluences up to  $\sim 3 \times 10^{15} N_{eq}/cm^{-2}$ 
  - Source tests. Dac settings and trimming procedure not 100% settled
- Fluences up to  $\sim 5 \times 10^{15} N_{eq}/cm^{-2}$ 
  - ATLAS IBL (same sensor concept and vendor)

Signal height and detection efficiency fully sufficient for the targeted radiation level of  $1.5 \times 10^{15} N_{eq}/cm^{-2}$  (~250fb<sup>-1</sup> in layer 1 at 3cm)



#### Sensor Inefficiency vs. Fluence and Voltage





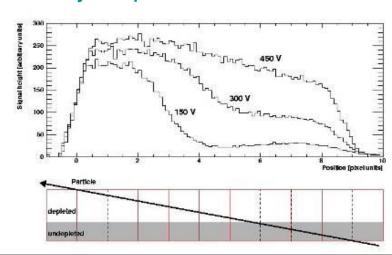
# **Degradation of spatial resolution**

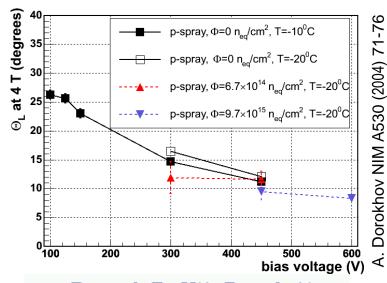
### Perpendicular to the beam axis

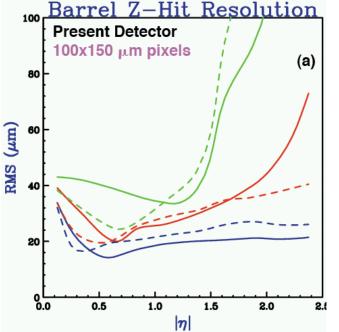
- Lorentz angle is reduced by higher bias voltage
- Process is slow and steady
- Well understood and measured since many years
- No way to prevent this (only smaller pitch)

### Along beam axis

- In irradiated samples the shape of cluster has to be taken into account "template algorithm")
- If fluence is too high/signal too low:
  - fluctuations might lead to "hole" in the clusters
  - present software cannot "glue" to clusters together
  - large errors in position determination
  - Only measure are lower thresholds (new digital ROC)
- Presently the operational limit of the detector







Morris Swartz, JHU, taken from the draft TDR]



## Present activities to characterize degradation

#### Irradiation in 2012 at KIT

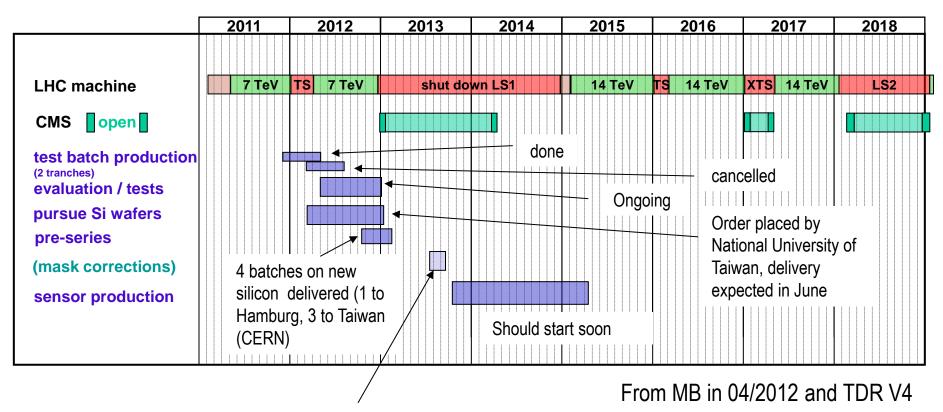
- Several samples were irradiated to  $1.5 \times 10^{15} N_{eq}/cm^{-2}$ (250fb<sup>-1</sup>) and  $3 \times 10^{15} N_{eq}/cm^{-2} (500fb^{-1})$ Samples were tested in a DESY-testbeam end of March
- - Activity was performed by ETHZ (Rossini, Hits) and Santander (F. Munoz), special thanks to Daniel
- Good data taken for  $1.5 \times 10^{15} N_{eq}/cm^{-2}$ 
  - Different bias (300V-1000V)
  - Angle 0 and 80 degree
  - Thresholds 40, 60, 80 (in Vcal units, digital ROC will allow for lower thresholds)
- Data for higher fluences (and 3D sensors) was taken, but might have timing issues
- Analysis of data just started (M. Rossini)



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# Schedule for sensor production



Layout of the sensors "frozen" (unchanged compared to the present).

Different size of passivation openings depending on bump vendor (done)

No wishes for special alignment structures addressed to me

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- Present BPIX sensors suitable for Phase I upgrade
- •Exact characterization of samples irradiated to 1.5E15 N<sub>eq</sub>/cm<sup>2</sup> (250 fb<sup>-1</sup>) ongoing
  - •Data taken at test beam in Hamburg in March
- Quality of Topsil silicon and polishing is verified (4 batches)
- •It is time to place the 1st production order



PSI, A0@43202012



# Barrel sensor concept (n-in-n)

### **Collect electrons (n-side readout)**

Trapping, Lorentz angle but n-side isolation

### Avoid problems in module design

- N-Substrate → double sided processing
- · All sensor edges on ground potential

### Pixel cell layout

- Moderated p-spray with bias grid (insensitive area)
- Small gaps, homogenous drift field, higher C ~ 80fF

#### Wafer

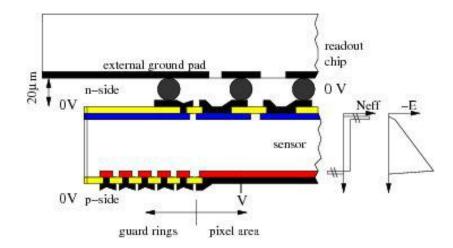
- FZ (plus Oxygen diffusion) <111>
- Phosphorous doped (n-type), 2-5 kΩcm
  - Present BPIX from single Wacker crystal
  - TOPSIL crystal (~1100 Wafer) ordered

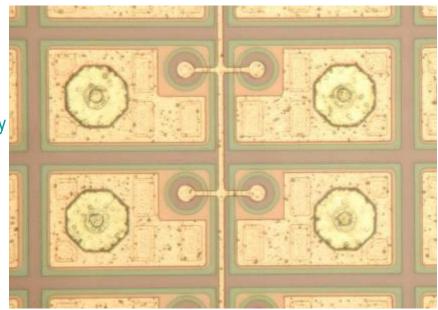
#### **Module**

- IV curve is very sensitive and a good indicator of device quality
- $I(V=150V) < 2 \mu A$  (typical value ~1 $\mu A$ )
- Slope I(V=150V)/I(V=100V) < 2
- I(V=150) should be stable in time

Test structures (measured only if there is a "reason")

- Diode:  $CV \rightarrow Vdepl \rightarrow \rho$  in specs
- V<sub>punch-through</sub> > 3V
- Sheet resistance of n<sup>+</sup> and p<sup>+</sup> < 500 Ω/sqr</li>





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